| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L1 | 0 | (mask$3 and (trench$2 or groove$1 or recess$2) and oxide and isolat$3 and silcion and nitride and active and etch$3 and faster).clm. | US-PGPUB | OR | ON | 2005/08/22 12:27 |
| L2 | 3 | (mask$3 and (trench$2 or groove$1 or recess$2) and oxide and isolat$3 and silicon and nitride and active and etch$3 and faster).clm. | US-PGPUB | OR | ON | 2005/08/22 12:30 |
| L3 | 383 | (438/400,597,586,424,296,221,453. ccls.) and "2005".py. | US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB | OR | ON | 2005/08/22 12:29 |
| L4 | 2601 | (trench$2 or groove$1 or recess$2) and isolat$3 and etch$3 and faster and oxide | US-PGPUB | OR | ON | 2005/08/22 12:31 |
| L5 | 16 | 3 and 4 | US-PGPUB | OR | ON | 2005/08/22 12:30 |
| L6 | 3906 | (trench$2 or groove$1 or recess$2) and etch$3 and faster and oxide | US-PGPUB | OR | ON | 2005/08/22 12:31 |
| L7 | 19 | 6 and 3 | US-PGPUB | OR | ON | 2005/08/22 12:31 |